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~~06/04/2008~~

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DOCKET NO: 263788US2PCT

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF :  
KEISUKE KAWAMURA, ET AL. : EXAMINER: ARANCIBIA, M. G.  
SERIAL NO: 10/519,475 :  
FILED: DECEMBER 28, 2004 : GROUP ART UNIT: 1792  
FOR: APPARATUS FOR PLASMA :  
PROCESSING, METHOD OF  
PROCESSING SUBSTRATE  
THEREWITH, APPARATUS FOR  
PLASMA-ENHANCED CHEMICAL  
VAPOR DEPOSITION, AND METHOD  
FOR FILM FORMATION THEREWITH

AMENDMENT UNDER 37 C.F.R. § 1.116

COMMISSIONER FOR PATENTS  
ALEXANDRIA, VIRGINIA 22313

SIR:

In response to the Office Action dated January 29, 2008, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 8 of this paper.